

means for filling the ablated portions of the substrate with a substantially absorbent material; and

means for removing additional portions of the substrate while permitting selected portions of the substrate to remain.

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CONT  
19. The system of claim 18 further including an objective lens positioned between the phase mask and the substrate.

20. The system of claim 18 wherein the ablating means includes means for forming a complex pattern of ablated portions of the substrate.

21. The system of claim 18 wherein the ablating means includes means for forming a pattern of ablated portions of the substrate designed to match a pattern of an image detector with which the anti-scatter x-ray grid can be used.

REMARKS

Claims 13 and 14 have been canceled, claim 10 has been amended, and claims 18-21 have been added. Examination of claims 10-12 and 15-21 is respectfully requested.

Respectfully submitted,

  
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